

Thin Film Growth: the Effects of Electronics and Kinetics

Peter Czoschke

Advisor: Prof. Tai-Chang Chiang

In partial fulfillment of the requirements of the
Preliminary Examination

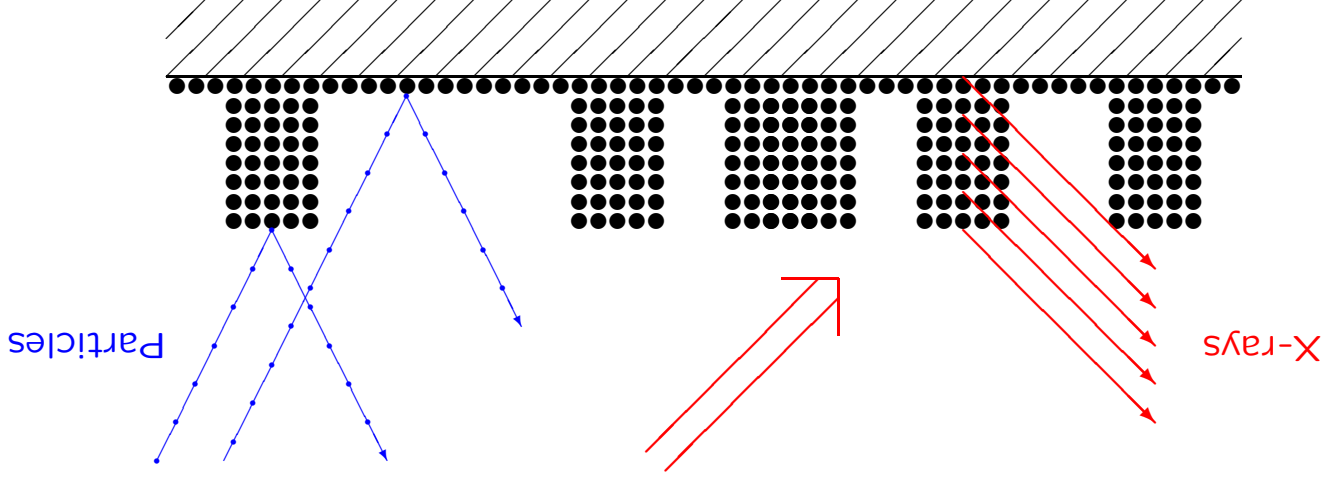
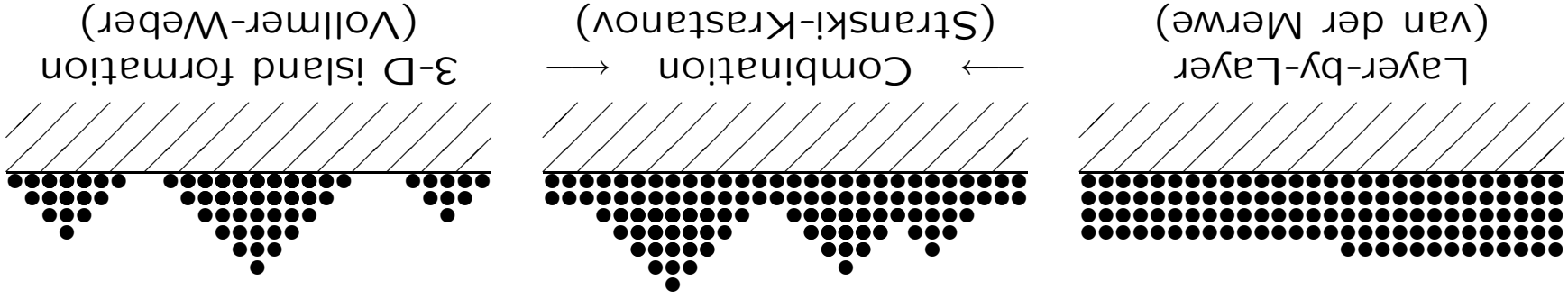
May 2, 2003



Outline

- Motivation
- Experimental Apparatus
- Surface X-ray Diffraction (SXRD)
- Quantum Size Effects (QSE) and Quantum Confinement
- I. Layer Relaxations in Pb/Si(111)
- II. Temperature-Dependent Growth Studies
- Summary

Thin Film Growth



?????

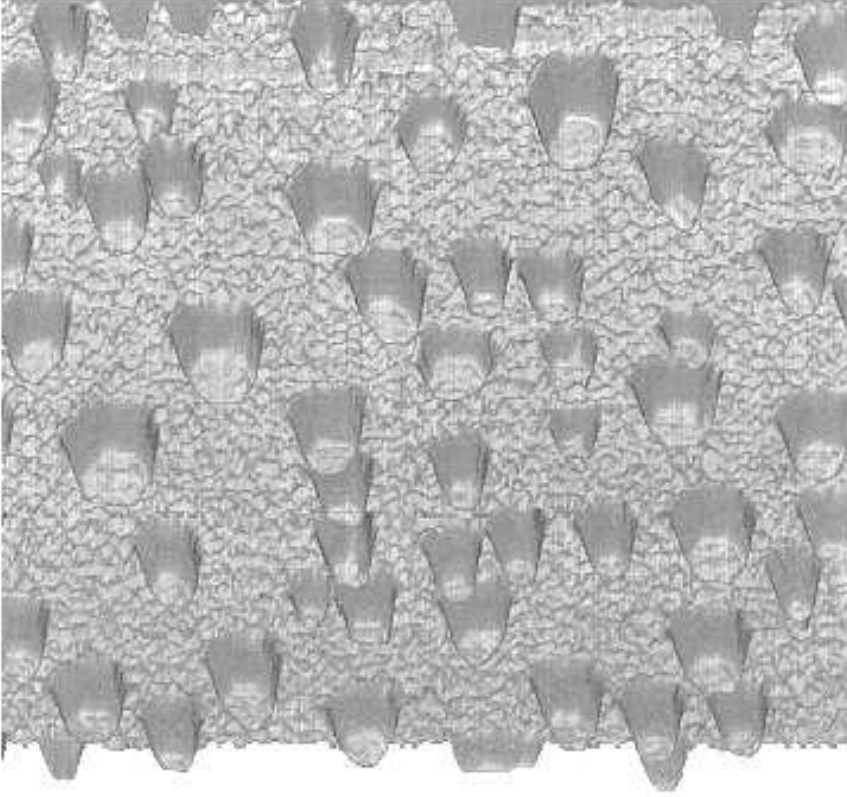
Quantum confinement of electronic states



Preferred thicknesses

Quantum Size Effects in Pb/Si(111)

- Island heights appear to be highly uniform \Leftrightarrow preferred thicknesses
- Self-organization attributed to QSE
- Morphology depends on:
 - \leftarrow Temperature
 - \leftarrow Pb coverage
 - \leftarrow Pb/Si interface
 - \leftarrow Kinetic pathway

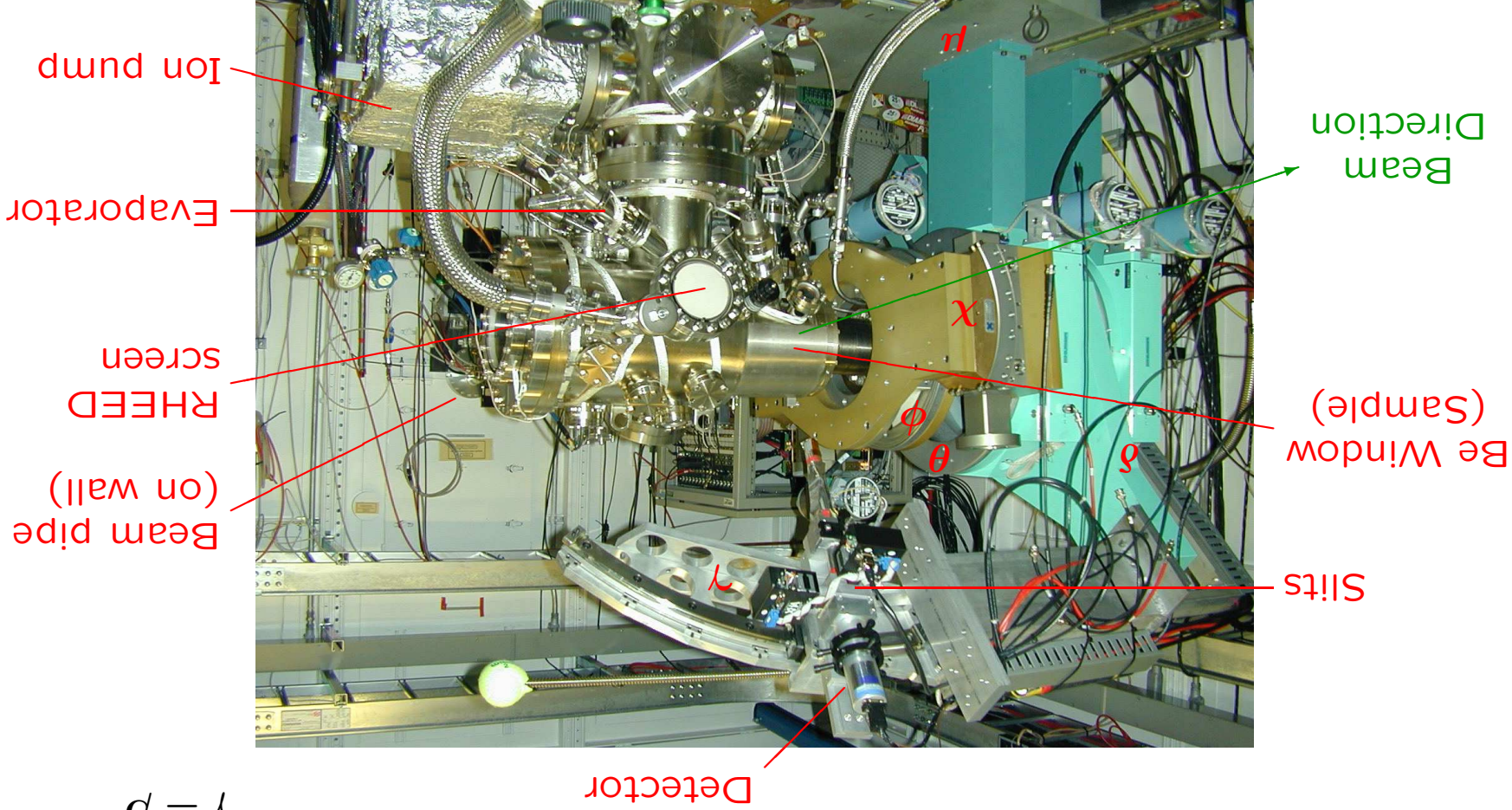


M. Hupalo, et. al., Surf. Sci. 493 (2001) 526

SXRD Chamber at Sector 33ID UNICAT, Advanced Photon Source

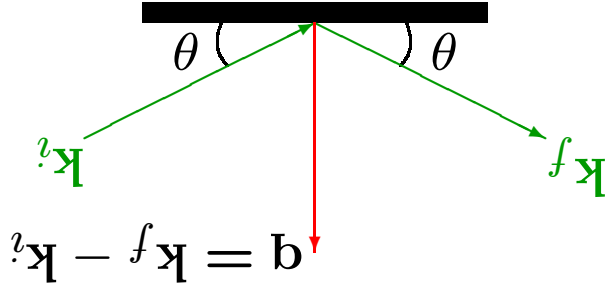
$$\mu \text{ (table)} = \alpha$$

$$\gamma = \beta$$



Surface X-ray Diffraction (SXRD)

Specular Reflectivity

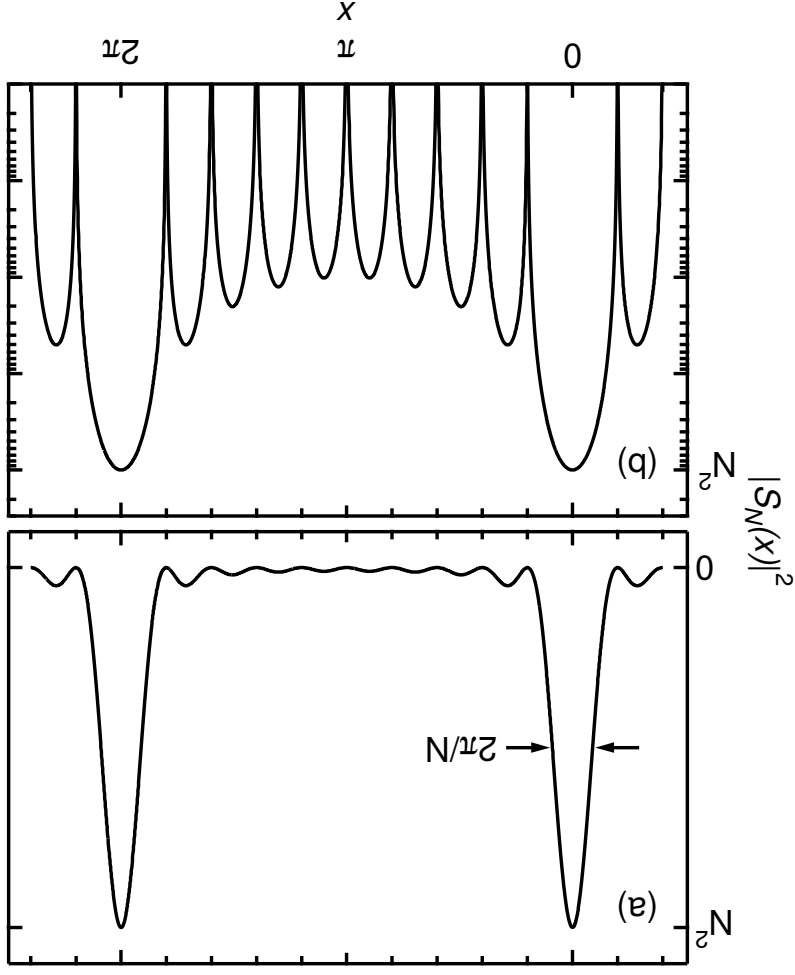


- Since $q \cdot a_1 = q \cdot a_2 = 0$, the specular rod is insensitive to in-plane order

- Thin film overlayers will contribute an amplitude similar to the N-slit interference function,

$$S_N(x) = \sum_{n=0}^{N-1} e^{inx}$$

- $x = 0, 2\pi \rightarrow$ Bragg peaks



N-Slit Interference Function

Interlayer Relaxations in Pb/Si(111)

- Previous STM study observed oscillations in step heights

- Step heights correlated with electronic effects

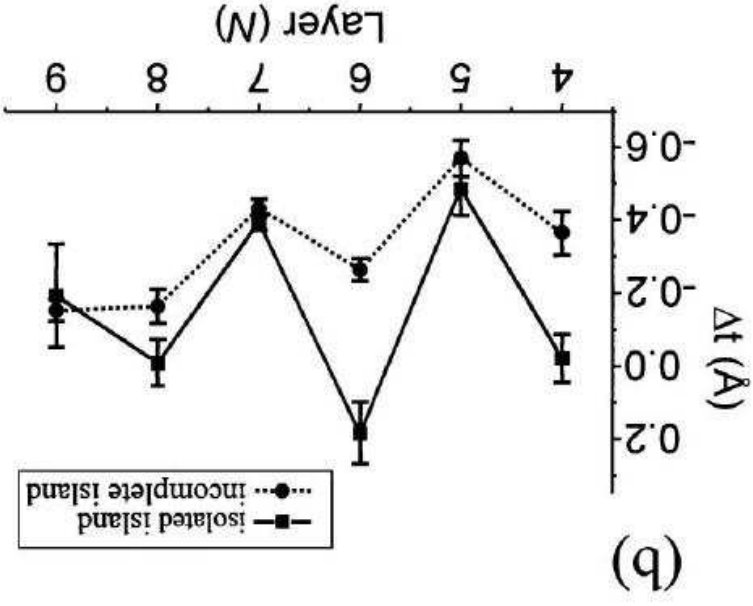
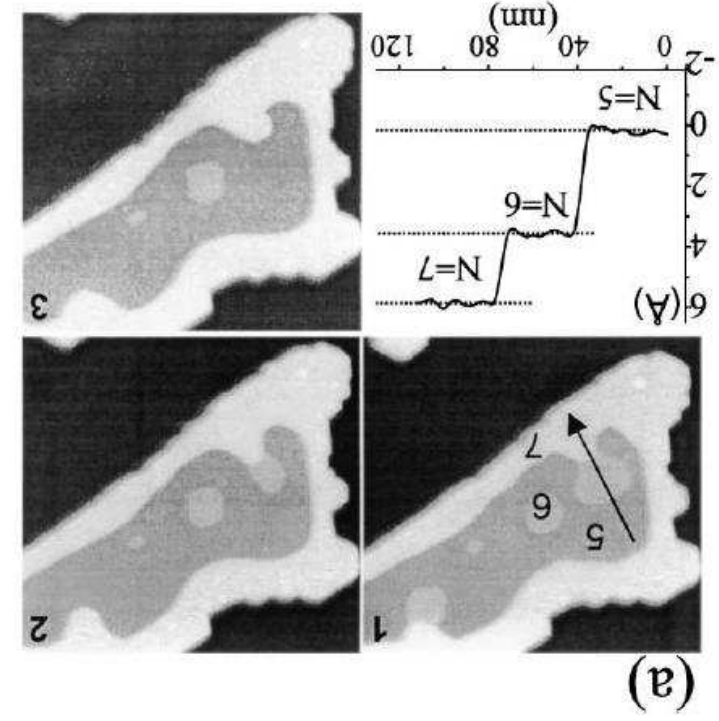
- But: step height \neq layer thickness

- Magnitude of layer relaxations?

- Penetration into film?

- Follow Friedel oscillations?

- Samples grown on different preferred thicknesses \Rightarrow different layer relaxations?



W. B. Su, et. al., PRL 86 (2001) 5116

Electron Confinement and Quantum Size Effects (QSE)

- Conduction electrons in thin metal films take on **particle-in-a-box**-like states

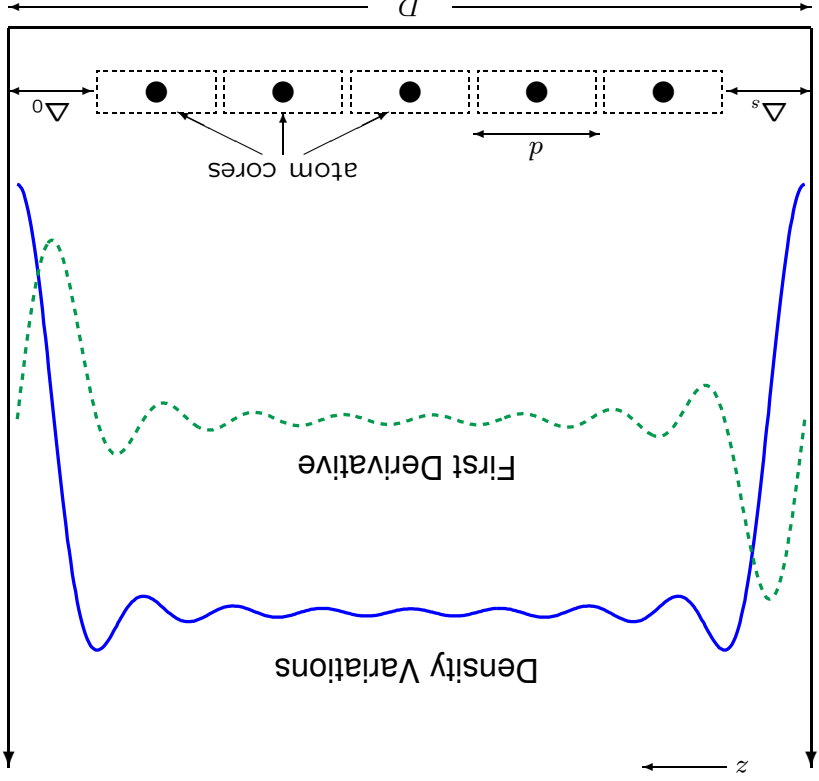
- Free-electron charge density exhibits **Friedel oscillations** in z -direction

- Oscillations have a wavelength $\approx \pi/k_F = \lambda_F/2$

$$\delta\rho(z) = \frac{1}{C_D} \left(k_F^2 + \frac{1}{\partial z^2} \right) S_D$$

$$\Delta_s(z) = A \frac{\partial}{\partial z} \delta\rho(z)$$

$$S_D = \frac{1}{2} \sin 2k_F z \cot \frac{D}{\pi z} - \sin^2 k_F z$$



SXRD Reflectivity Model for Pb/Si(111)

$$A(l) \propto G(\theta) \left[\overbrace{f_{Si}(l) e^{-2M_{Si}l}}_{\text{Si substrate}} \frac{1 - e^{-2\pi i l/3}}{1 + e^{-2\pi i l/12}} + \overbrace{\sum_N \theta_N \sum_{j=1}^N e^{2\pi i l z_{j,N}}}_{\text{Pb film}} \right]$$

A range of different island heights $\{N\}$ is used with occupancies θ_N . The atom z -positions are determined via the free-electron model:

$$z_{j,N} = \sum_{l=1}^N \left[p + \Delta t (\Delta_s + n - \frac{z}{l}) p \right]$$

where

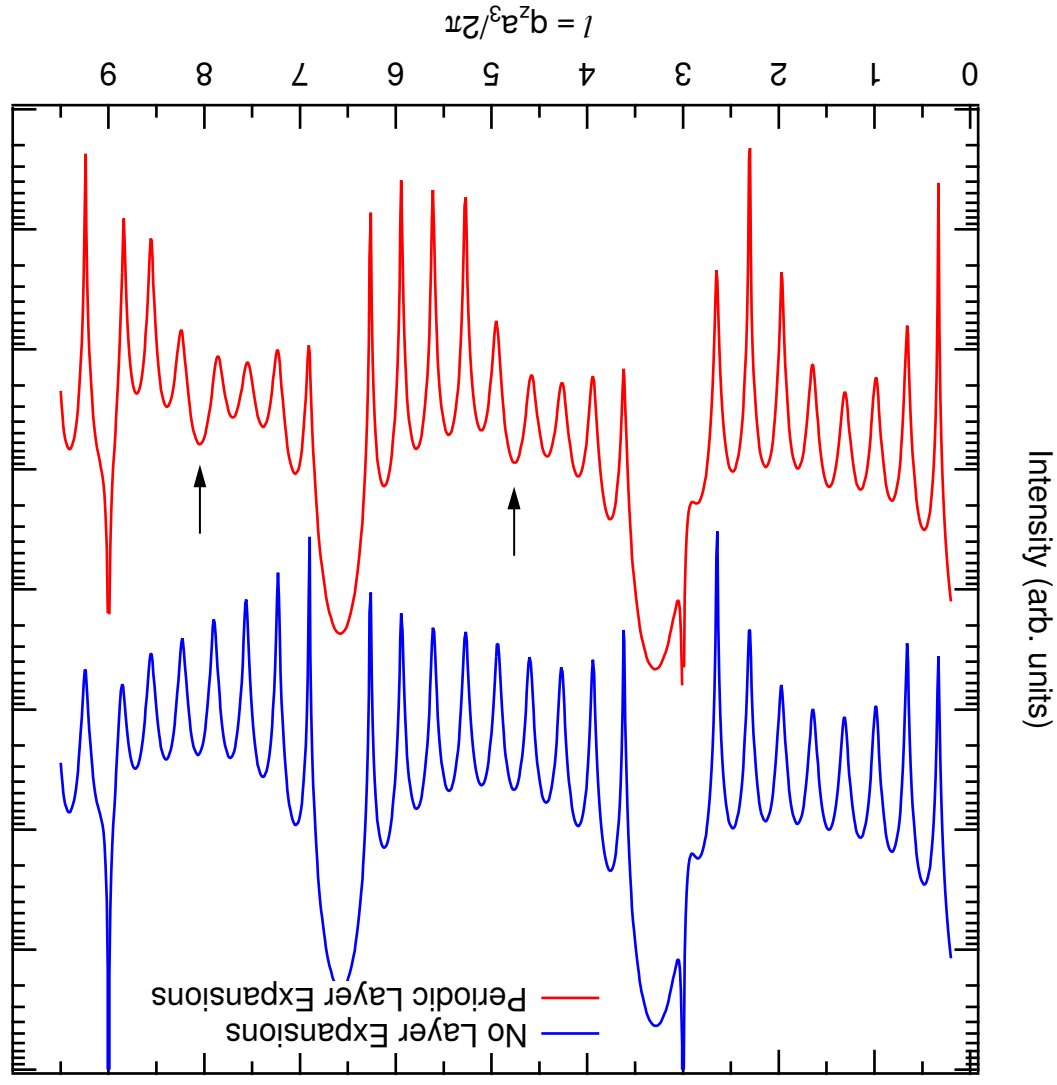
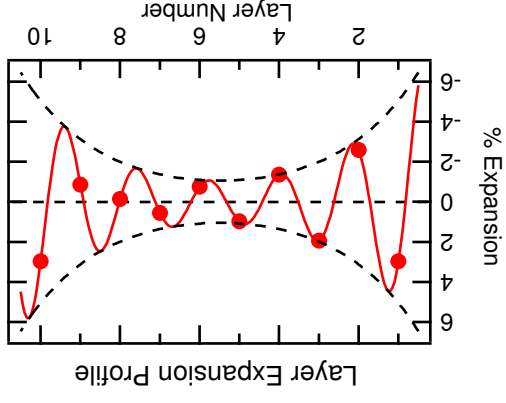
$$\Delta t(z) = \Delta_s(z) + p - \Delta_s(z)$$

Parameters: scaling factor, $A, \delta d, \Delta_0, \Delta_s, \{\theta_N\}, M_{Pb}$

SXRD Reflectivity Simulations

- Simulations are for 10 ML Pb on Si(111)-7x7
- For Pb(111), $\lambda_F/2 \approx 1.8d$
- Used simplistic sinusoidal model for z_j

- Half-order features appear with expansions

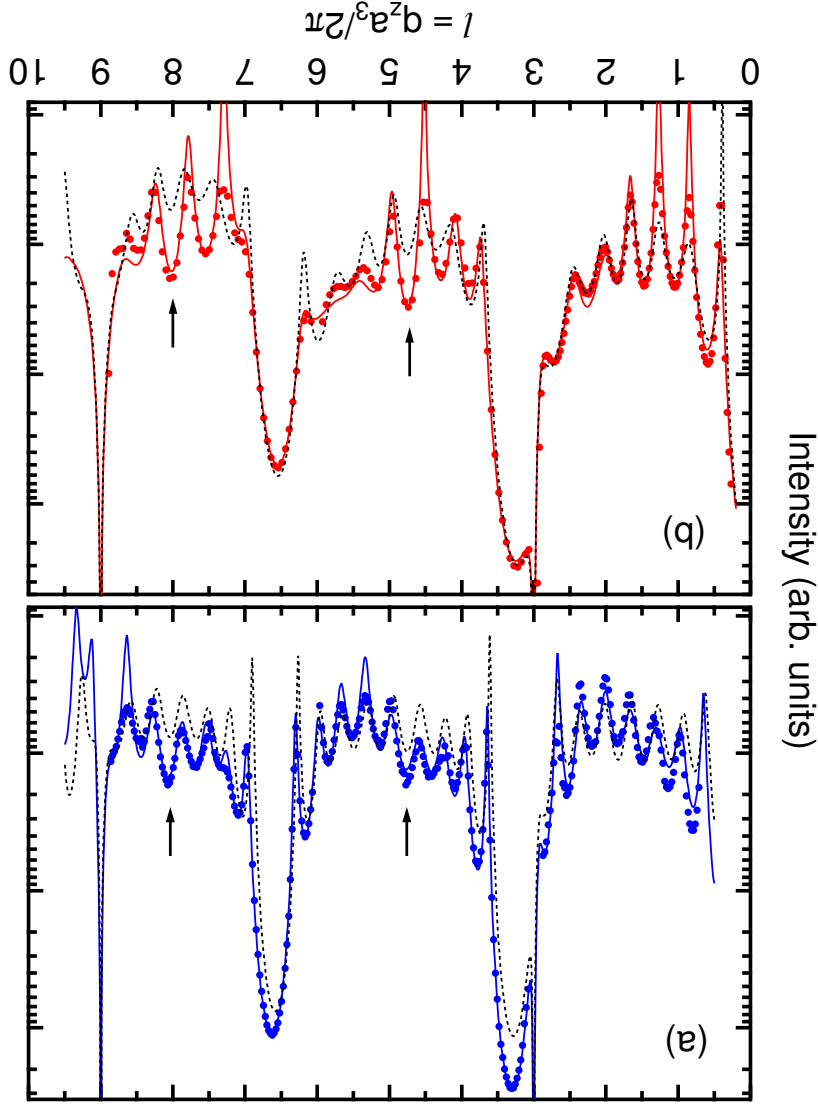


Layer Relaxations in Pb/Si(111)

- Pb was deposited on both the 7×7 and $\sqrt{3} \times \sqrt{3}$ - β interfaces
- Profiles were fit with a range of island heights to allow for a non-uniform distribution
- Profiles were fit with and without ($A = 0$) layer relaxations \Rightarrow half-order features not reproduced without layer relaxations

(a) 8.5 ML Pb on Si(111)- 7×7
 Deposited at 185 K
 $N = 10$ islands

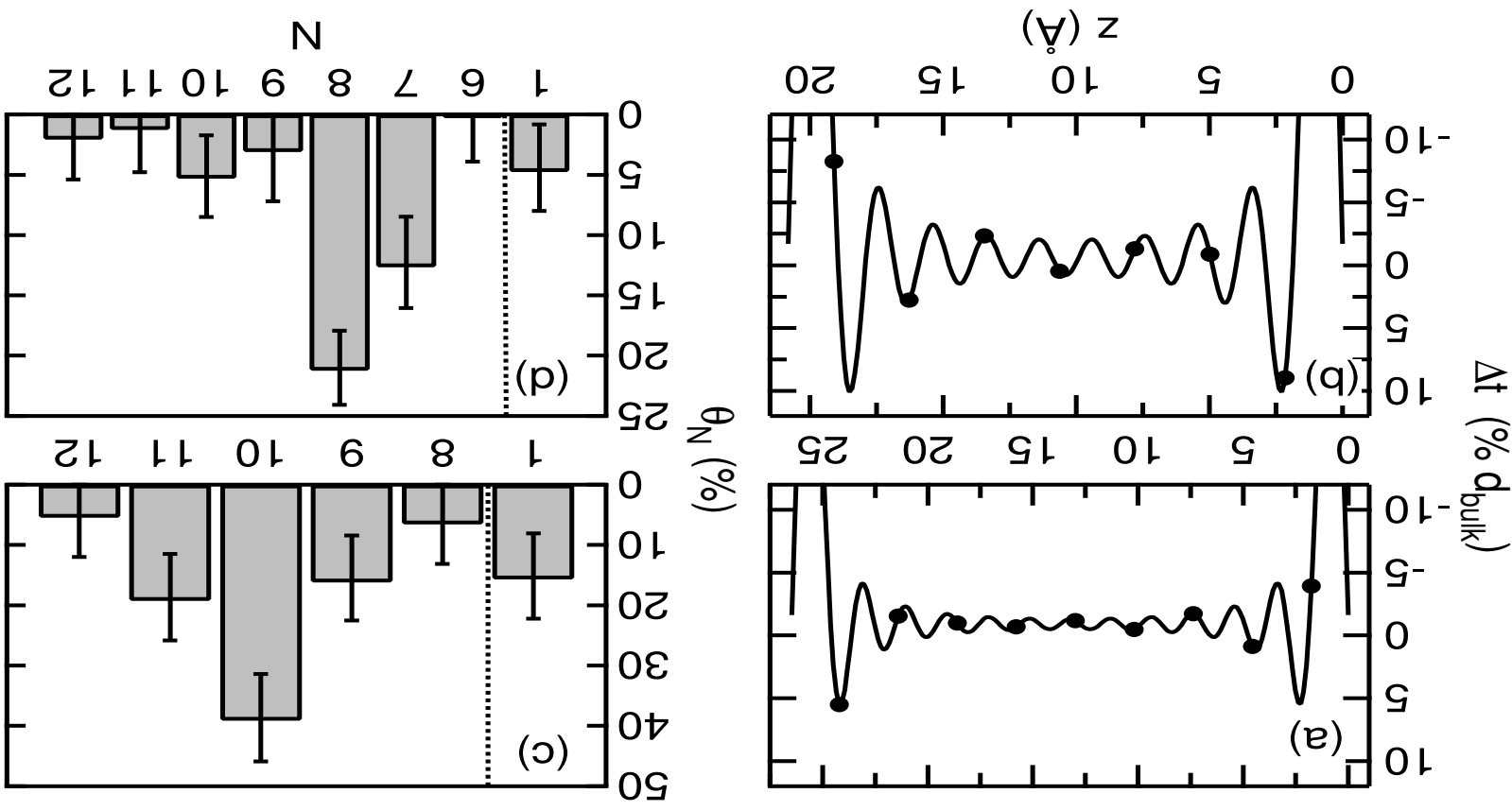
(b) 4.5 ML Pb on
 Pb/Si(111)- $\sqrt{3} \times \sqrt{3}$ - β
 Deposited at 115 K
 Annealed to 180 K
 $N = 8$ islands



Layer Relaxation Results

- More data needed for trends
- Oscillatory relaxations appear

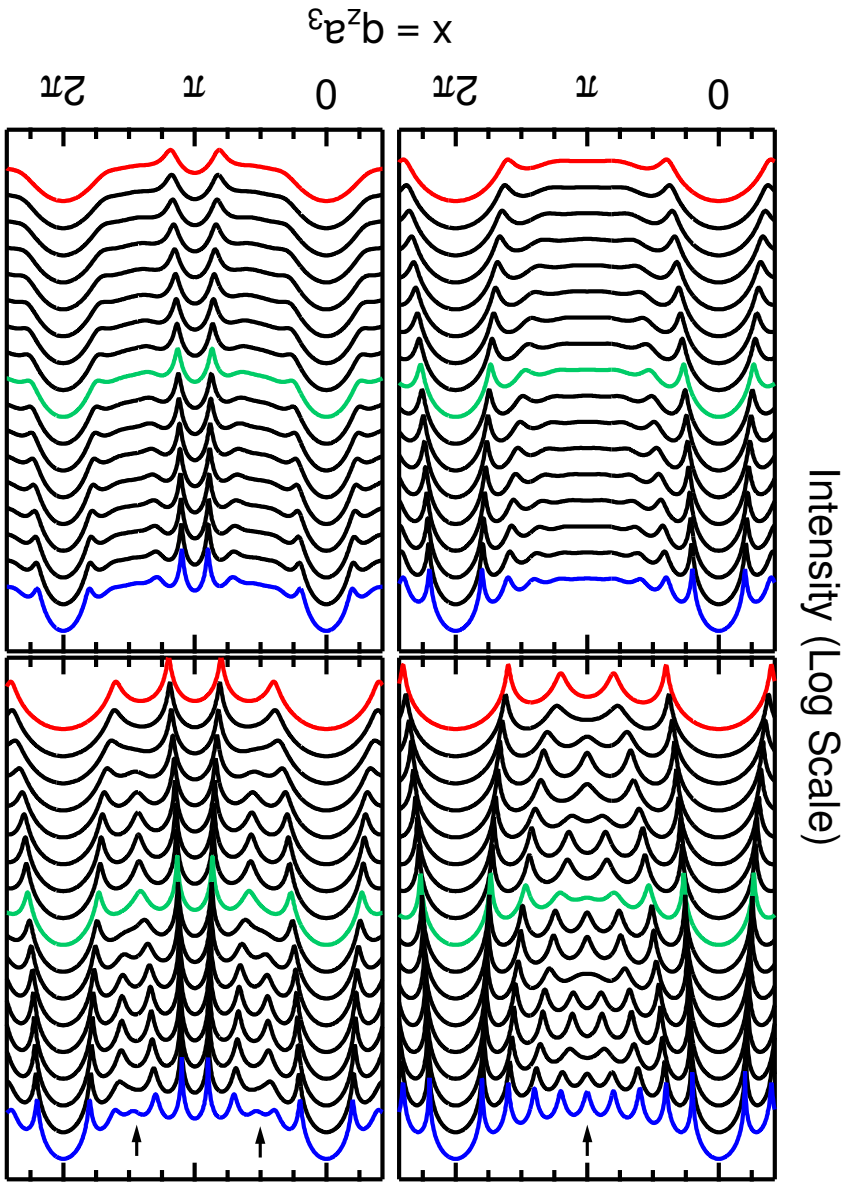
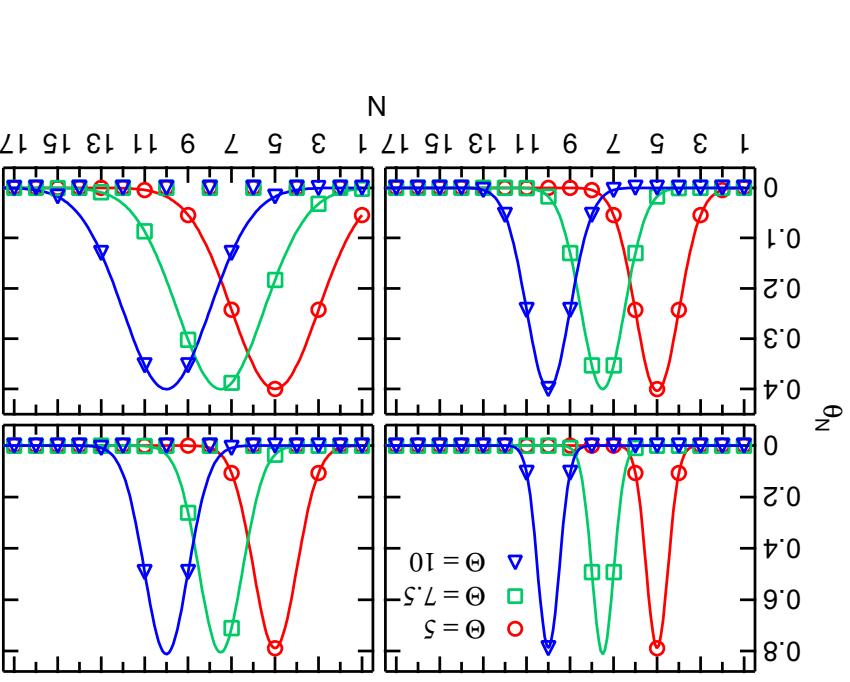
Parameter	7×7	$\sqrt{3} \times \sqrt{3}$
A (\AA^2)	86 ± 35	135 ± 35
Δ_s (\AA)	0.36 ± 0.05	0.76 ± 0.25
Δ_0 (\AA)	0.90 ± 0.40	0.31 ± 0.08
δd (%)	-0.90 ± 0.31	-0.77 ± 0.65



Island Growth

- Growth curve model: $A(qz) = \sum_{N=1}^{\infty} \theta_N S_N(qz)$

- Monolayer vs Bilayer growth
- Distribution of island heights



Island Growth Example — Pb/Si(111)

- Started with 4.5 ML Pb on Pb/Si(111)- $\sqrt{3} \times \sqrt{3}$ - β

- Primary island height evolves as $T \nearrow$: $N = 5 \rightarrow 6 \rightarrow 8 \rightarrow 10 \rightarrow \dots$

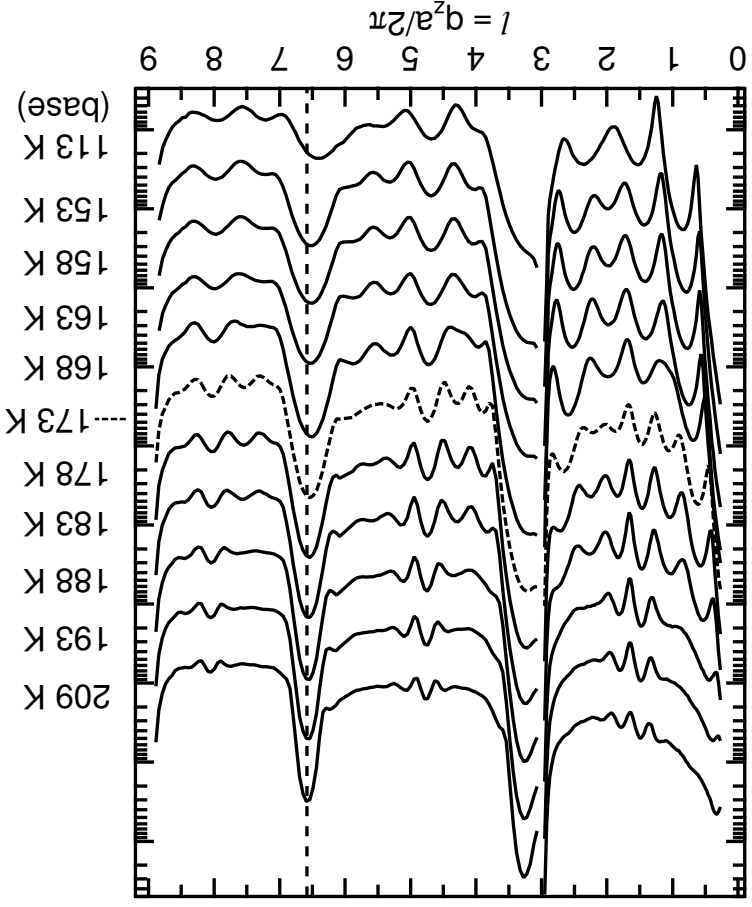
- Bilayer height selection even as film roughens

- Movement of Pb peak at $l \approx 6.4$ to $6.6 \Rightarrow$ layer spacing becoming bulk-like

- As $T \nearrow$, islands grow irreversibly \Rightarrow kinetics

- Expect interface dependence

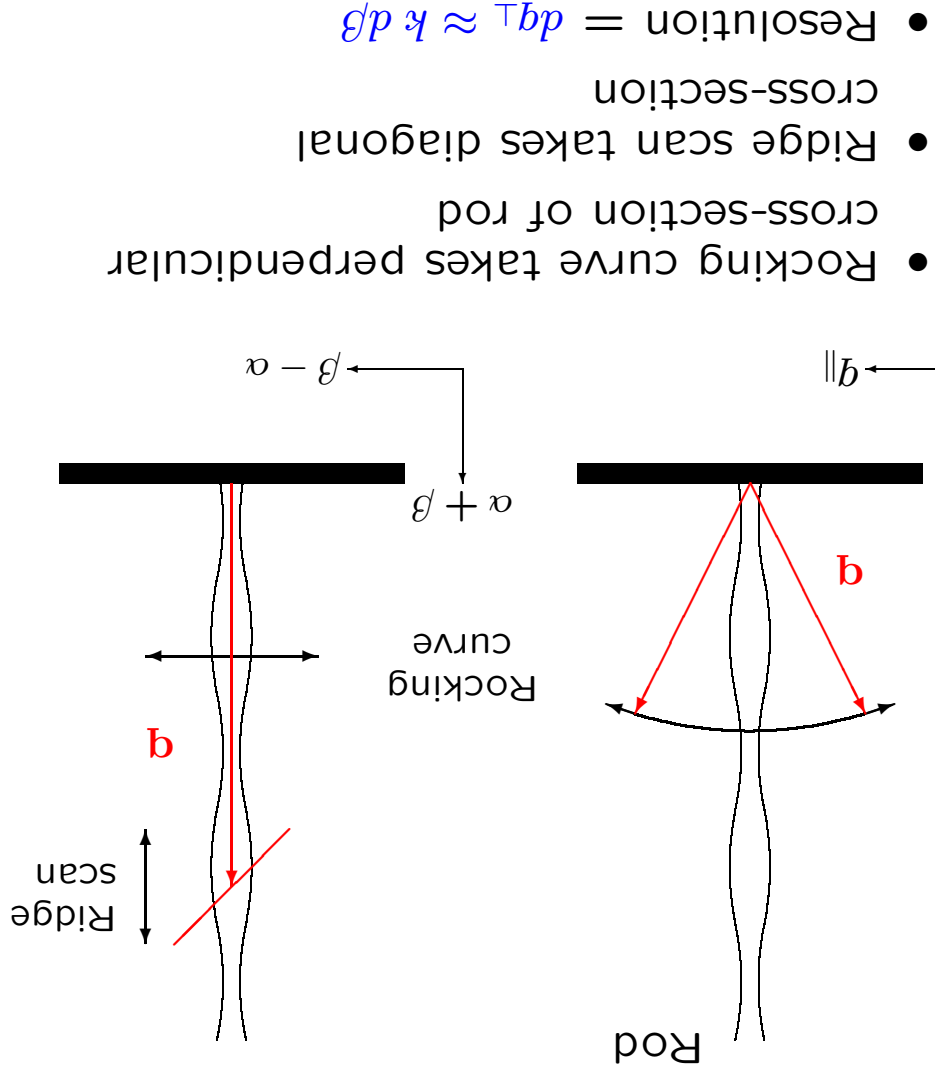
- Application to other systems: Ag/Si, Ag/GaAs, Pb/Ge, Ag/Fe?



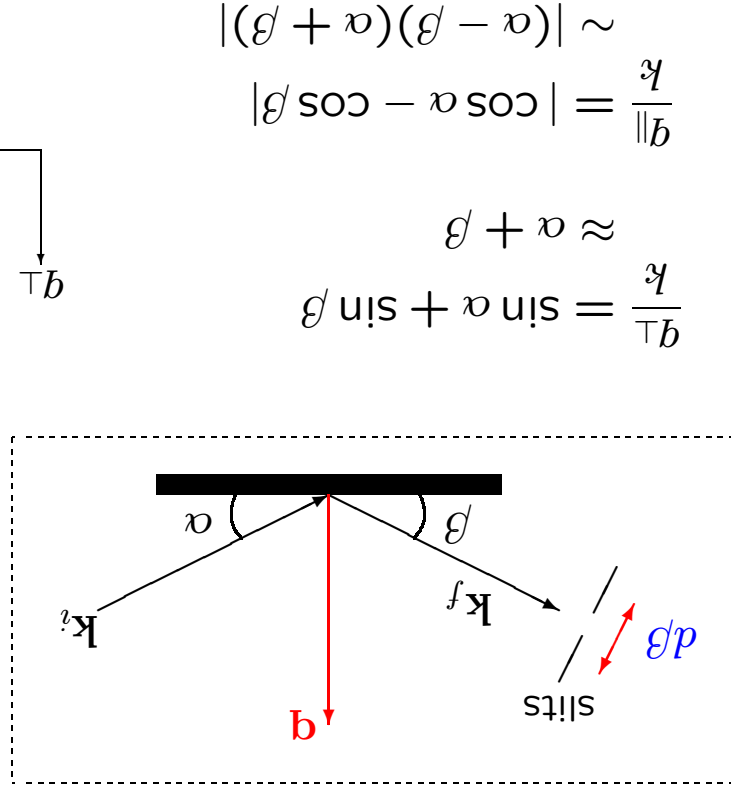
Summary

- Unusual growth behavior has been observed in thin metal films \Rightarrow attributed to QSE
- Electronic confinement can lead to preferred thicknesses as well as characteristic structural effects
- Both electronic (thermodynamic) and kinetic effects important
- Proposed experiments:
 1. Layer relaxations in Pb/Si(111)
 2. Studies of island growth with temperature
- Need more data

Measuring Reflectivity



- Rocking curve takes perpendicular cross-section of rod
- Ridge scan takes diagonal cross-section
- Resolution = $dp_{\perp} \approx k d\beta$



$$\sin \alpha + \sin \beta = \frac{k}{b_{\perp}}$$

$$\alpha + \beta \approx \frac{k}{b_{\perp}}$$

$$|\cos \alpha - \cos \beta| = \frac{k}{b_{\parallel}}$$

$$\sim |(\alpha - \beta)(\alpha + \beta)|$$

X-ray Integrated Intensity

electron: $A(R, t) = -A_0 r_0 \frac{R}{e^{ikR}} \cos \phi$

distrib.: $A(\mathbf{q}) = -A_0 \frac{R}{r_0} \sum_{\mathbf{r}_j} e^{i\mathbf{q} \cdot \mathbf{r}_j}$

$r_0 = \frac{4\pi\epsilon_0 mc^2}{e^2} = 2.82 \times 10^{-5} \text{ \AA}$

$I(\mathbf{q}) = I_0 \frac{R^2}{r_0^2} |F(\mathbf{q})|^2$

Integrated Intensity (total energy measured by detector)

$$E = \iiint I(\mathbf{q}) dt R^2 d\beta d\gamma$$

$\beta, \gamma = \text{angular directions of slits}$

$$= \iiint_{R^2} I(\mathbf{q}) \frac{\omega}{R^2} d\alpha d\beta d\gamma$$

scan from α to $\alpha + d\alpha$ in time t

What we really want is the integral in reciprocal space, $\int d\mathbf{q}$

$$= I_0 \frac{r_0^2}{\omega} \iiint |F(\mathbf{q})|^2 J^{-1} dq_x dq_y dq_z$$

where J is the Jacobian for the transformation $\alpha, \beta, \gamma \rightarrow q_x, q_y, q_z$

$J^{-1} = \text{"Lorentz Factor"}$

Free-Electron Density in a Quantum Well (Expanded)

$$(1) \quad \rho(z) = \frac{2V}{2\pi} \int_0^{k_F} \rho_3 \mathbf{k} |\psi_{\mathbf{k}}(z)|^2 \sum_2^n \delta(k_z - \frac{D}{\pi n})$$

$$(2) \quad = \sum_{n_0}^{n=1} 2\pi (k_z^F - k_z) \sin^2 k_z z$$

$$(3) \quad \rho(z) \equiv \frac{\langle \rho(z) \rangle_z}{\langle \rho(z) - \langle \rho(z) \rangle_z \rangle_z}$$

$$(4) \quad = \frac{\sum_{n_0}^{n=1} (k_z^F - k_z)}{\sum_{n_0}^{n=1} (k_z^F - k_z) \cos 2k_z z}$$

$$(5) \quad = \frac{1}{n_0} \sum_{n_0}^{n=1} \left(k_z^F - \left(\frac{D}{\pi n} \right)_2 \right) \cos \left(\frac{D}{2\pi n z} \right)$$

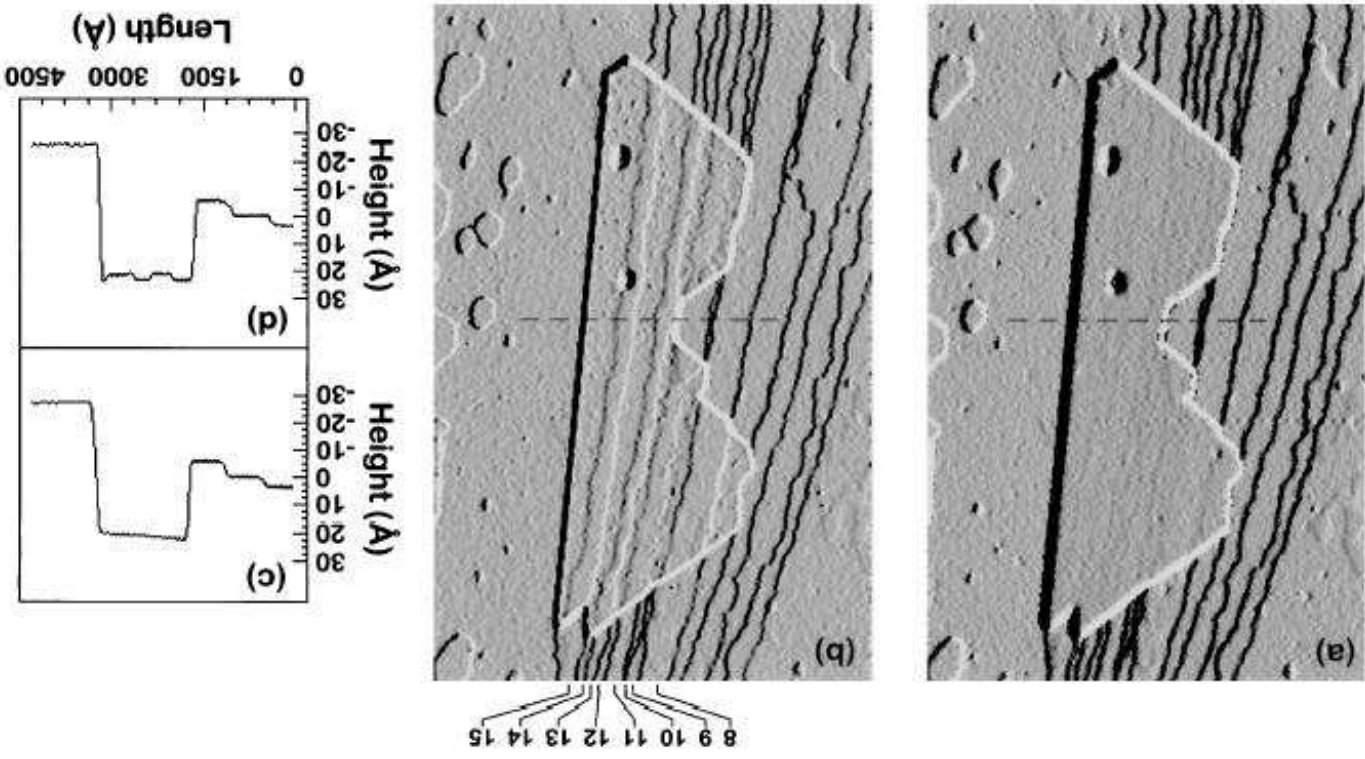
$$(6) \quad = \frac{1}{1} \left(k_z^F + \frac{1}{\partial z} \frac{4\partial z z}{2} \right) S_D(2\pi z/D)$$

$$(7) \quad \Delta s(z) = -\frac{C_D}{A} \left(k_z^F \frac{\partial z}{\partial} + \frac{1}{\partial^3} \frac{4\partial z z}{3} \right) S_D(2\pi z/D)$$

$$(8) \quad \Delta t(z) = -\frac{C_D}{A} \left(k_z^F \frac{\partial z}{\partial} + \frac{1}{\partial^3} \frac{4\partial z z}{3} \right) \left[S_D \left(\frac{D}{2\pi(z+p)} \right) - S_D \left(\frac{D}{2\pi z} \right) \right]$$

Charge Spillage into Vacuum

- STM images taken with different biases: (a) -5 V (b) $+5$ V
- (a) \leftrightarrow "real" island topology
- (b) \leftrightarrow electron fringes showing variable spillage of charge density into the vacuum



I. B. Altfelder, et. al., Phys. Rev. Lett. 78 (1997) 2815

Rocking Curves vs. "Ridge" Scans

